

Title (en)
ENERGY EMISSION SYSTEM FOR PHOTOLITHOGRAPHY

Title (de)
ENERGIE-EMISSIONSSYSTEM FÜR PHOTOLITHOGRAPHIE

Title (fr)
SYSTEME D'EMISSION D'ENERGIE POUR PHOTOLITHOGRAPHIE

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Application
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Abstract (en)
[origin: WO9951357A1] An emitted energy system is provided. The emitted energy system (10) may include a fluid (34) communicated through a nozzle (22). The fluid (34) communicated through the nozzle (22) may form a fluid plume (40). An input energy (64) may be applied to the fluid (34) in the fluid plume (40). The input energy (64) may excite the fluid (34) in the fluid plume (40) into producing an emitted energy (16). The emitted energy (16) is collected and directed by an output optics (18) to a target (20). In one embodiment, the target (20) is a photolithography system interface (68) for fabricating a semiconductor device (70). A remotely-controlled XYZ micro-positioning stage (620) facilitates alignment of the nozzle (510) and the diffuser (512) to the radiated energy beam.

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